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## INFORMATION DISCLOSURE CITATION

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Applicant	Kei WATANABE, et al.		
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U.S. PATENT DOCUMENTS						
Examiner Initial*	Document Number	Issue Date	Name	Class	Sub Class	Filing Date If Appropriate
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MT	6-302704	10/1994	Japan			No
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MT	Richard Swope, et al., "Improvement of Adhesion Properties of Fluorinated Silica Glass Films by Nitrous Oxide Plasma Treatment," Journal of the Electrochemical Society, Vol. 144, No. 7, July 1997, pp. 2559-2564
MT	Kwon et al., "Semiconductor Device Having Improved Metal Line Structure and Manufacturing Method Therefor," U.S. Application Publication No. 2001/0006255 A1, published July 5, 2001

Examiner	Michael Train	Date Considered	8/28/04
*Examiner:	Initial if reference considered, whether or not citation is in conformance with MPEP 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.		
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